

Polarimetric Raman instrumental development and Stress measurement application by using polarized Raman spectroscopy

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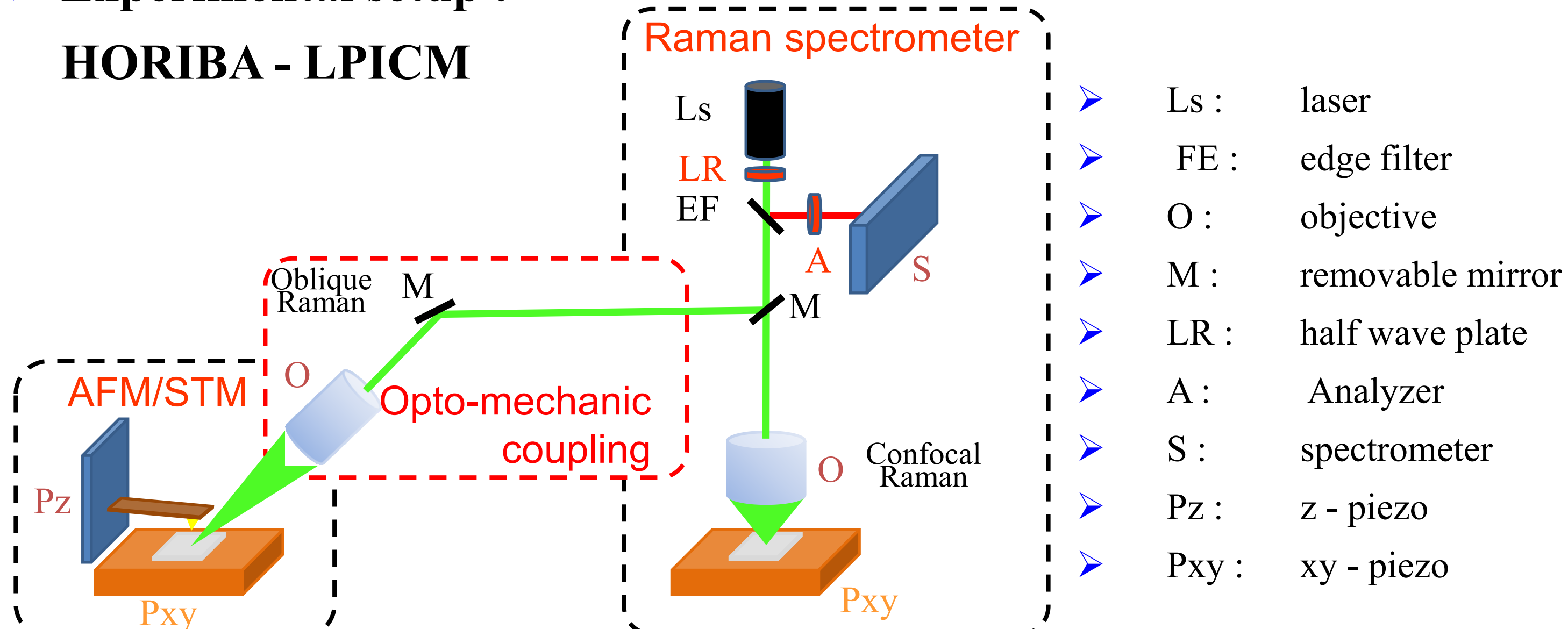
Scientific and technical objectives

CONTRAM: Determining the stress tensor through spatially resolved polarimetric Raman spectroscopy

- > Polarimetric Raman spectrometer development (LPICM, HORIBA Jobin Yvon)
- > Validation of the method by reference samples and techniques (LPICM, CEA-LETI)
- > Applications in the stress characterization to innovative structures (LPICM, CEA-LETI)
- > Applications in the stress characterization to semiconductor (Si, SiGe, Ge, GaAs...) and photonic structures (STM, 3SP, LPICM)

Stress measurement trough polarized Raman: from Si to SiGe and Ge

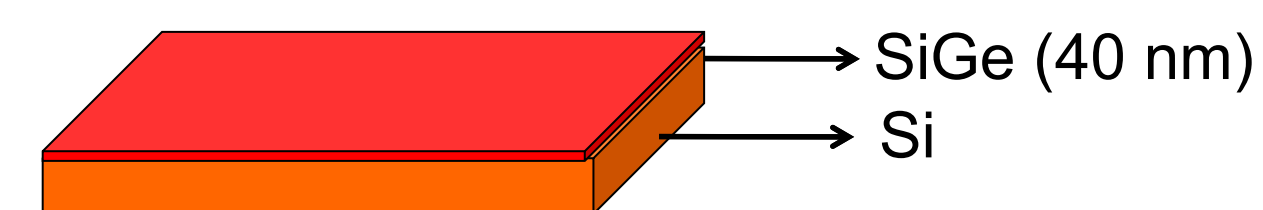
> **Experimental setup : HORIBA - LPICM**



- > Ls : laser
- > EF : edge filter
- > O : objective
- > M : removable mirror
- > LR : half wave plate
- > A : Analyzer
- > S : spectrometer
- > Pz : z - piezo
- > Pxy : xy - piezo

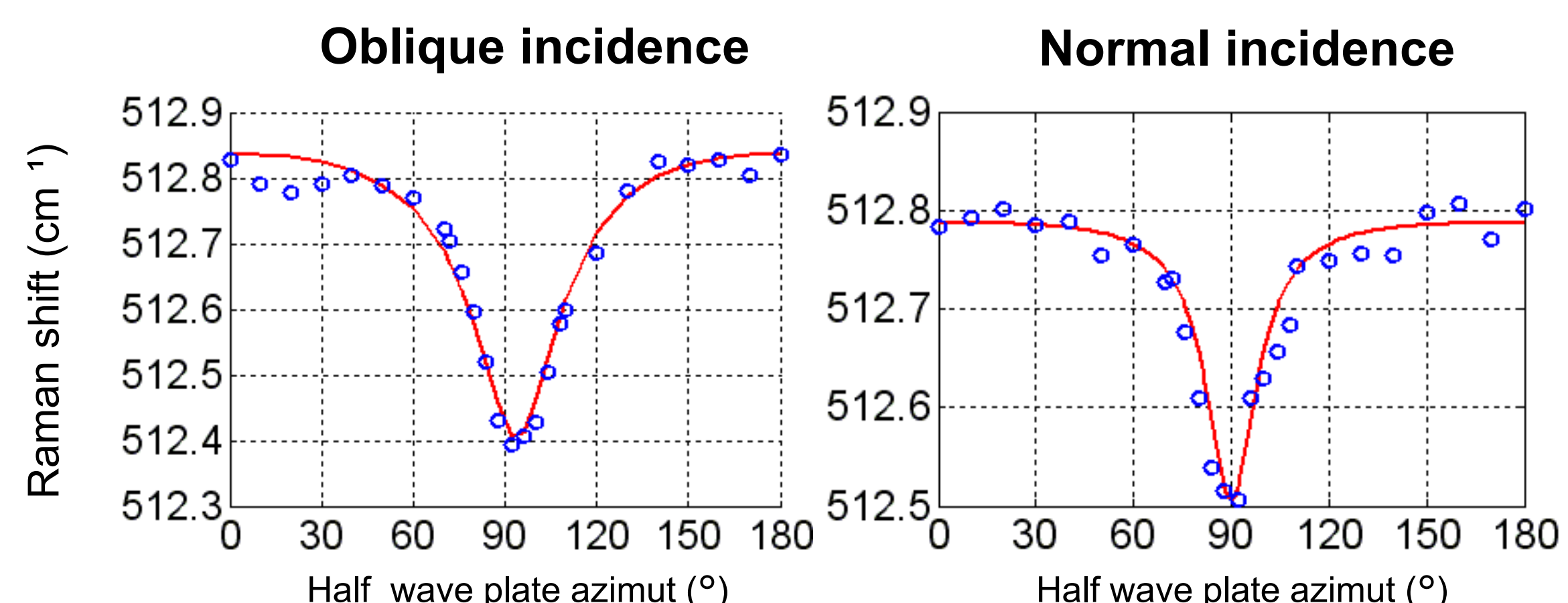
> **Samples and methodology of strain measurement**

SiGe deposited on Si substrate



- > Spectrum acquisition as function incident polarization orientation
- > Determining of Raman shift
- > Adjustment the results with the numerical model for strain or stress tensor identification

> **Results**



$$\sigma_{xx} = \sigma_{yy} = -041 \pm 0MPa \quad \sigma_{xx} = \sigma_{yy} = -030 \pm 0MPa$$

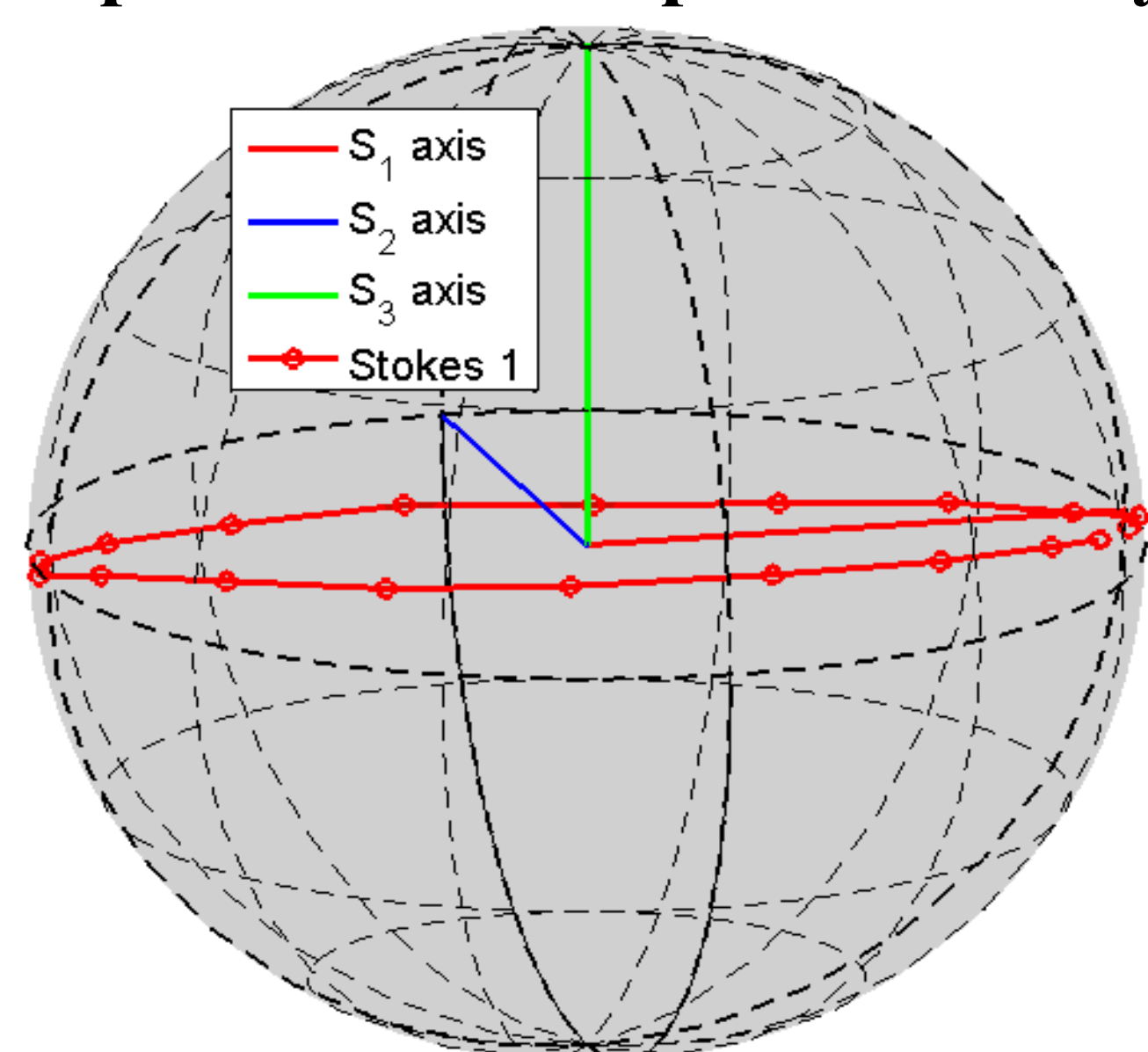
Oblique incidence → More accurate stress determination

From polarized Raman to polarimetric Raman...

> **Experimental methodology: polarimetric Raman calibration on Si band (521 cm⁻¹)**

To determine Stokes vectors (by Fourier Transform method), we insert in the detection (scattering) path before the analyzer, a rotating quarter wave plate. From 36 measurements at different orientations of the plate, we can determine the backscattering Stokes vector

> **Real polarimetric response of the system in Raman scattering**

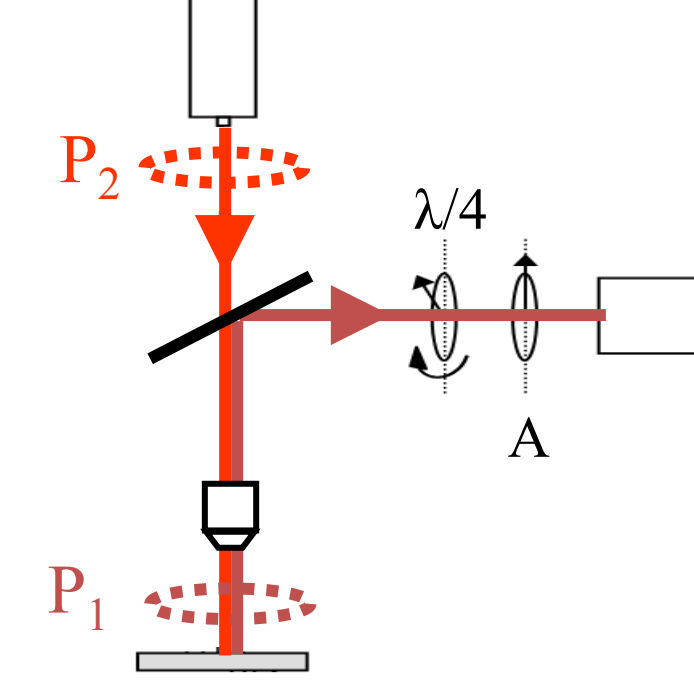


- > Confocal Raman configuration
- > $\lambda = 514.5 \text{ nm}$
- > Dop variation between 0.95 et 1
- > Three components [S_1 , S_2 , S_3] constitute ellipse and no united circle

- Presence of :
- > Depolarization
 - > Diatténuation
 - > Birefringence

Stokes vectors on Poincaré sphere for each orientation of P1

Modeling and characterization of the spectrometer response



Model :

- Exciting path : $M_{exc} = M_{\Delta} \cdot M_R \cdot M_{\Delta}$
- Scattering path : $M_{det} = M_R \cdot M_D \cdot M_{\Delta}$

- with :
- > M_D : linear diattenuator Mueller matrix
 - > M_R : linear birefringence Mueller matrix
 - > M_{Δ} : depolarizing element Mueller matrix

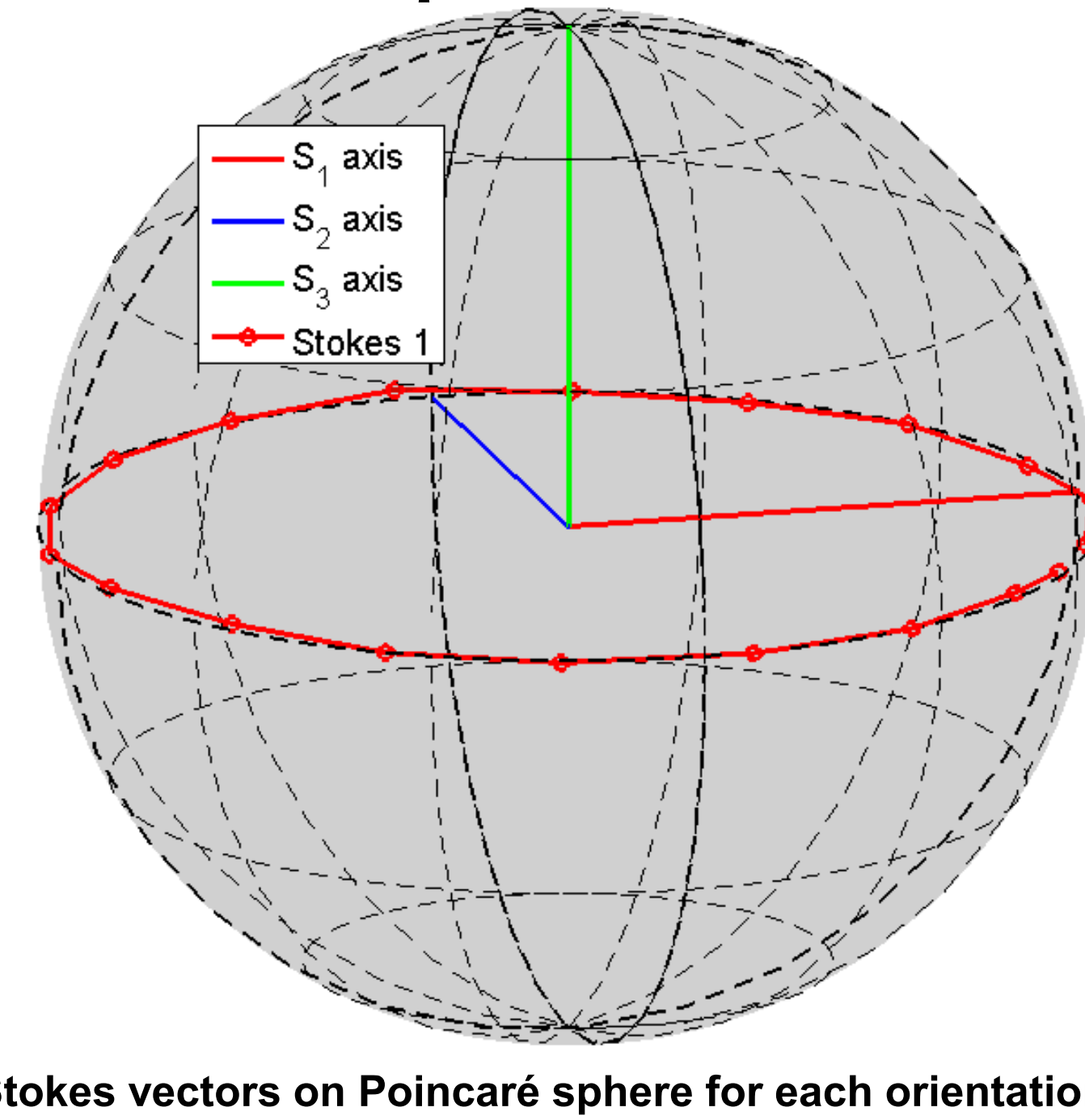
1. **Scattering path characterization :**

- > Rotating polarizer in position P_1 and measurement of the scattering Stokes vectors
- > Determination of M_{det} from : $\min_{R,D,\Delta} \left\| M_{det}^{-1} S_{mes} - \tilde{\gamma}_{theo} \right\|$

2. **Excitation path characterization :**

- > Rotating polarizer in position P_2 and measurement of scattering Stokes vectors
- > Determination of M_{exc} from : $\min_{\Delta, \gamma, R} \left\| M_{exc}^{-1} M_{det}^{-1} S_{mes} - \tilde{\gamma}_{theo} \right\|$

> **Polarimetric response after calibration**



Stokes vectors on Poincaré sphere for each orientation of P1

Parameters of the model :

Excitation :
 $[\Delta D R] = [0.987 \ 0.0069 \ -6.91 \ ^\circ]$
 Scattering :
 $[R D \Delta] = [10.88 \ ^\circ \ 0.01 \ 1]$

Accuracy of the model :

$\sigma_S = 10^{-2} [2.46 \ 3.3 \ 0.8]^T$
 $\sigma_{Dop} = 0.0074$

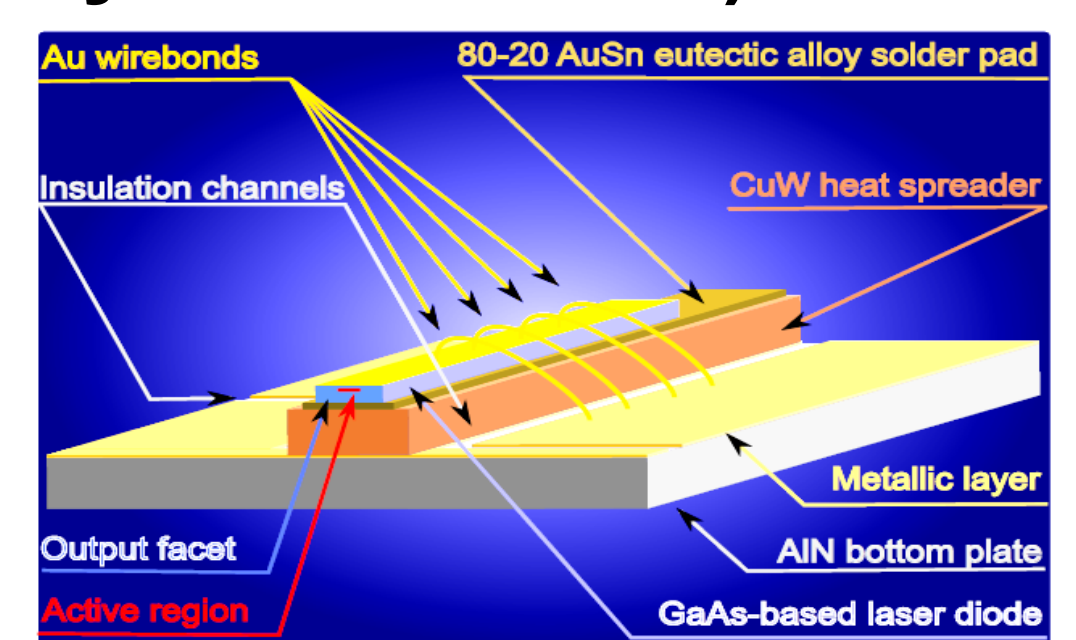
Final calibration of the polarimetric Raman

> **Problems :** Reducing the mechanical strain due to the transfer (deposition)

3S PHOTONICS RESULTS (with University of McMaster)

> **Samples**

- > High power laser diode AlGaAs/GaInAs
- > Plain AlN or original bi-material CuW/AlN
- > Lasts brazing in eutectic alloy AuSn [80-20 wt%]
- > « p-side up » assembly
- > Stress is due to the cooling of the assembly because of difference of thermal expansion coefficient and the dimensional disparities



> **Decreasing of the strain by bi-materials approach**

1. **Theoretical approach: Modeling by finite element method (FEM)**

- > 3D thermo-mechanics model
- > Mechanicals properties of materials
- > Simulation of brazing solidification → cooling from 280°C to 20°C
- > Determining of the **Stress tensor** → we show ($\sigma_z - \sigma_x$) (in Fig. 1)

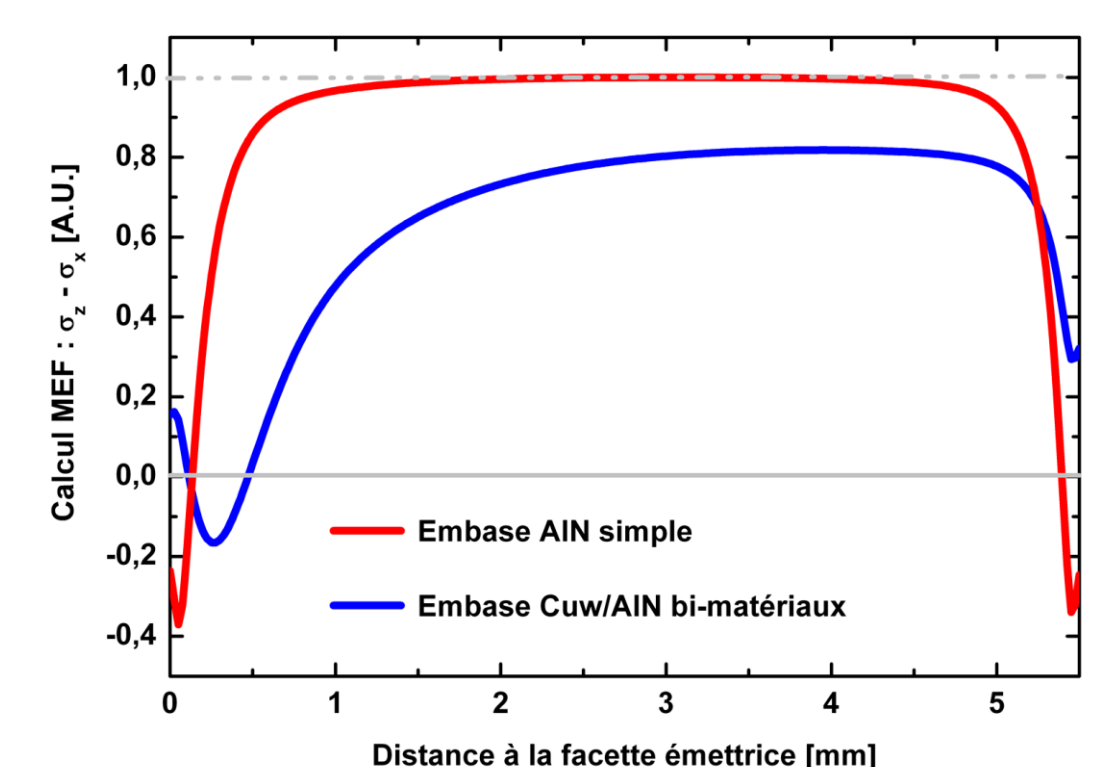


Figure 1 : Résultats MEF

2. **Experimental approach :** degree of polarization (DoP) measurement trough photoluminescence

- > Photoluminescence emitted by superior face of the plan diode AlGaAs/GaInAs
- > DoP is proportional to the difference of strain according to two axis of the studied plan

$$DoP = \frac{I_z - I_x}{I_z + I_x} = c_{sGa} \times \sigma_z - \tau_x \quad \mathbf{I}$$

> **Results**

- > FEM : Reducing the stress level to -20%
- > DoP : Reducing the stress level to -46%
- > **Double side effect** on bi-material submount

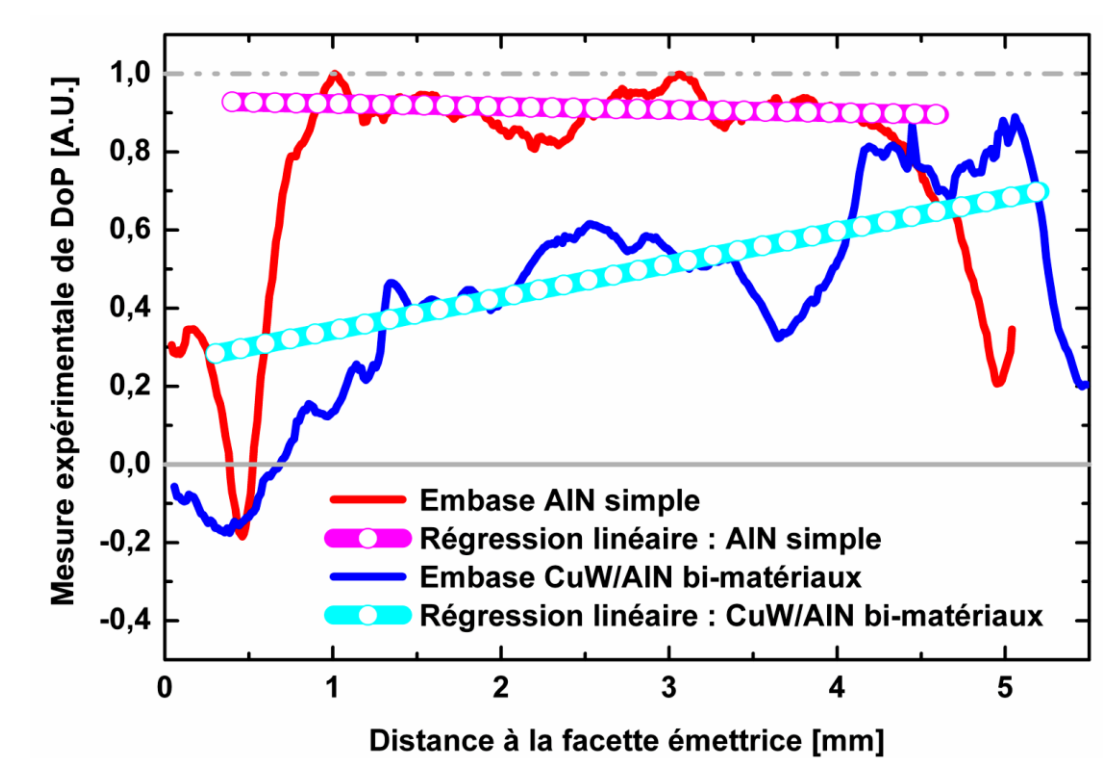


Figure 2 : Résultats expérimentaux

Results to be confirmed in polarized or polarimetric Raman by LPICM